

# CNT-based Thermal Interface Materials for Load-Bearing Aerospace Applications

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# Objective

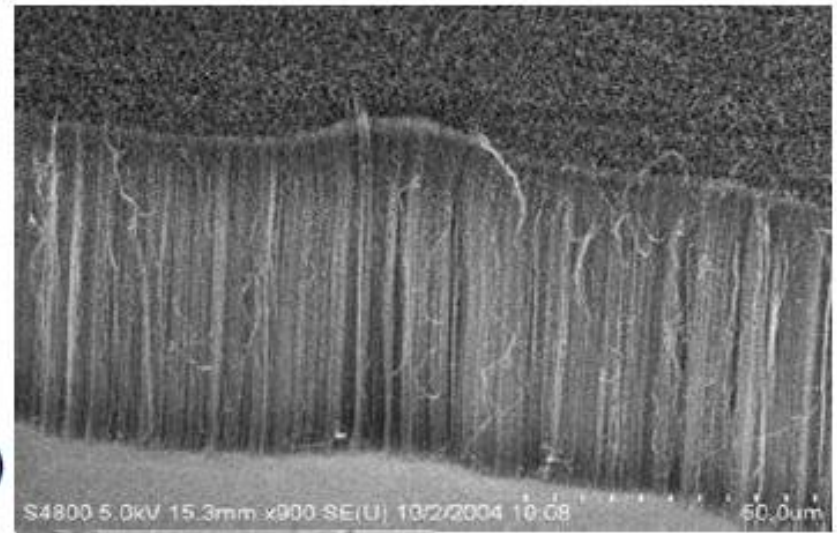
Develop multifunctional CNT-epoxy Thermal Interface Materials (TIMs) for load bearing aerospace applications.

## Emphasis -

To increase thermal transport across a thermal interface by utilizing an array of Vertically Aligned MWCNTs.

**Target  $k$  – 5 -7 W/(m-K)**

SEM picture of an array of vertically aligned carbon nanotube array grown on a silicon substrate.

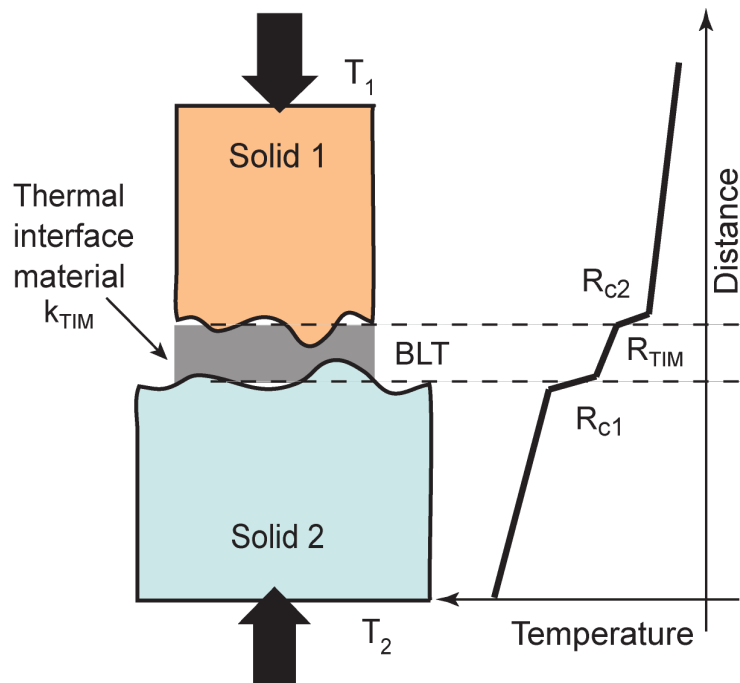


# Typical Thermal Interface

## Total Thermal Interfacial Resistance

$$R_{\text{interface}} = R_{c1} + \frac{BLT}{k_{\text{TIM}}} + R_{c2}$$

BLT – boundary layer thickness



## Minimize $R_{\text{interface}}$

$k_{\text{TIM}} \uparrow$

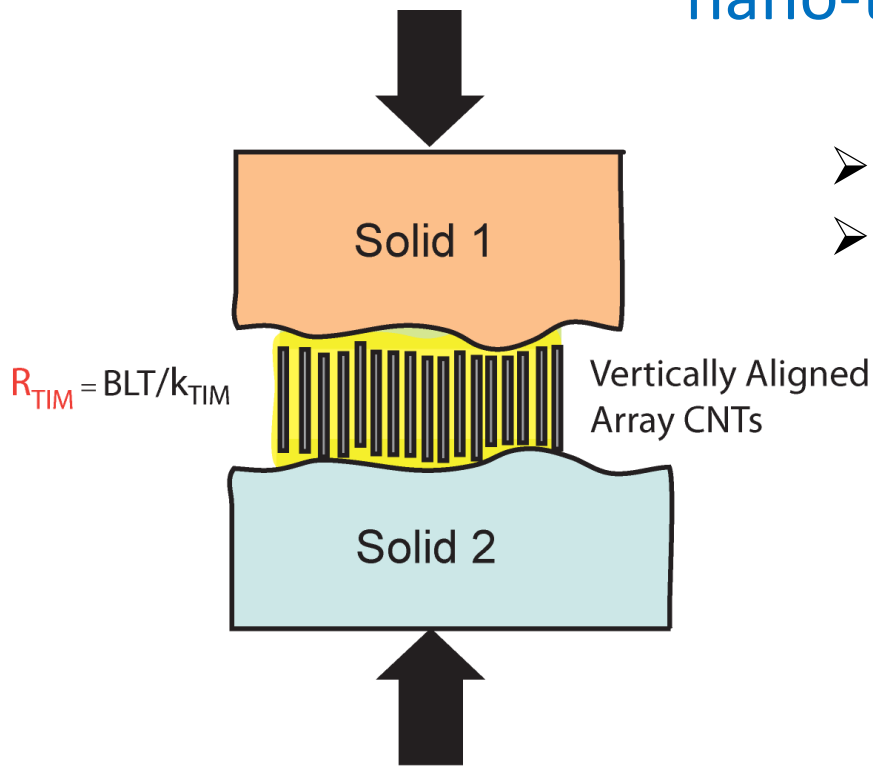
- Use high thermal conductivity fillers
- Minimize number of thermal interfaces

$R_c \downarrow$

- Reduce air gaps – use smooth contacting surfaces
- employ low melt-point materials (e.g. Sn), as capping layers
- materials with compatible phonon spectra

# Approach

## Vertically-aligned multi-wall Carbon nano-tubes in an epoxy matrix

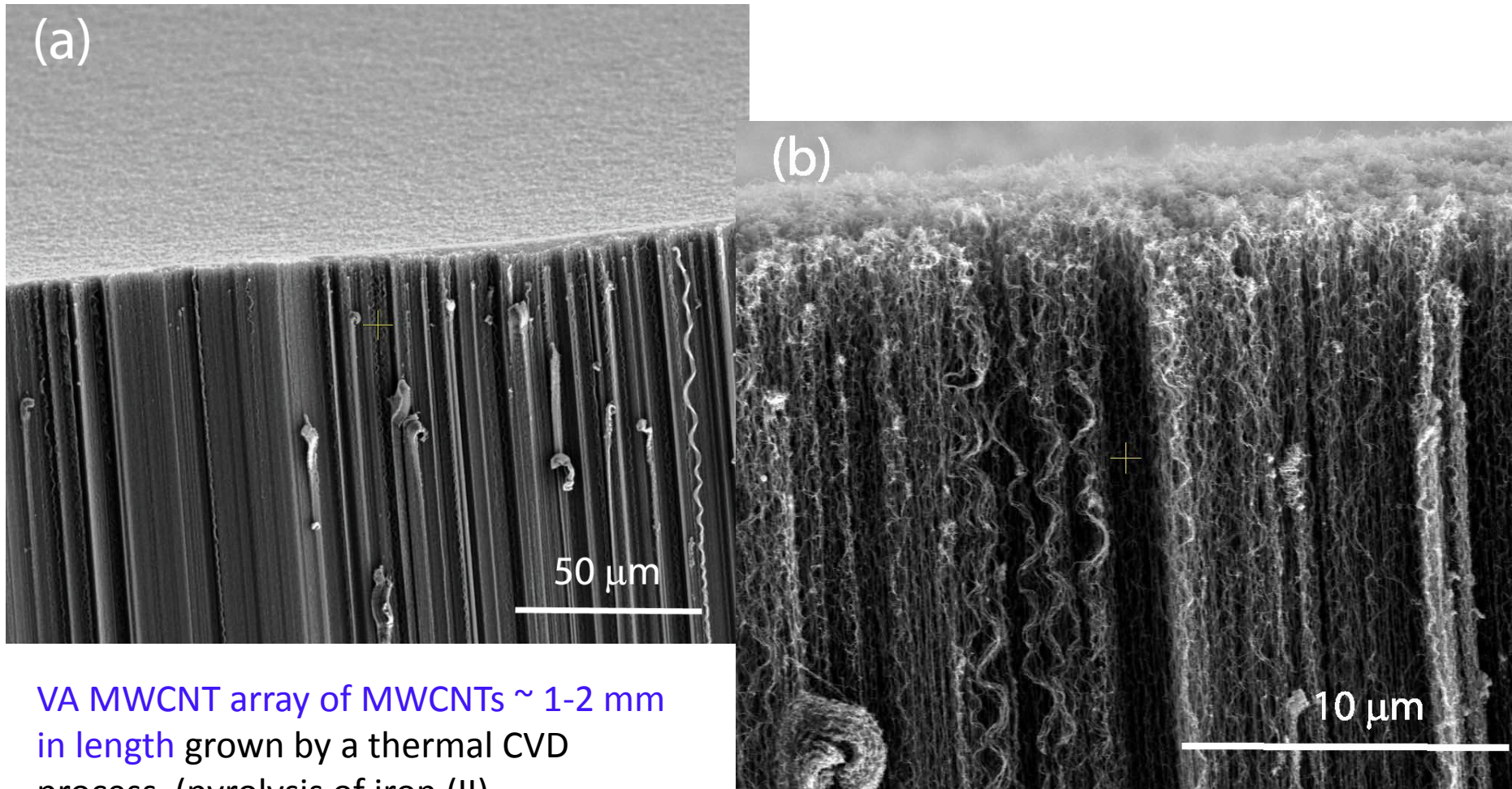


- $k_{CNT} \sim 100 \text{ W/m-K}$
- Use Sn capping metal layer to minimize phonon scattering at CNT-epoxy ends.

Assume 10% vol. fraction of VACNT in an epoxy matrix  
( $k_{epoxy} \sim 0.25 \text{ W/m-K}$ ;  $k_{CNT} \sim 100 \text{ W/m-K}$ )

$$k_{TIM} \sim 10 \text{ W/m-K}$$

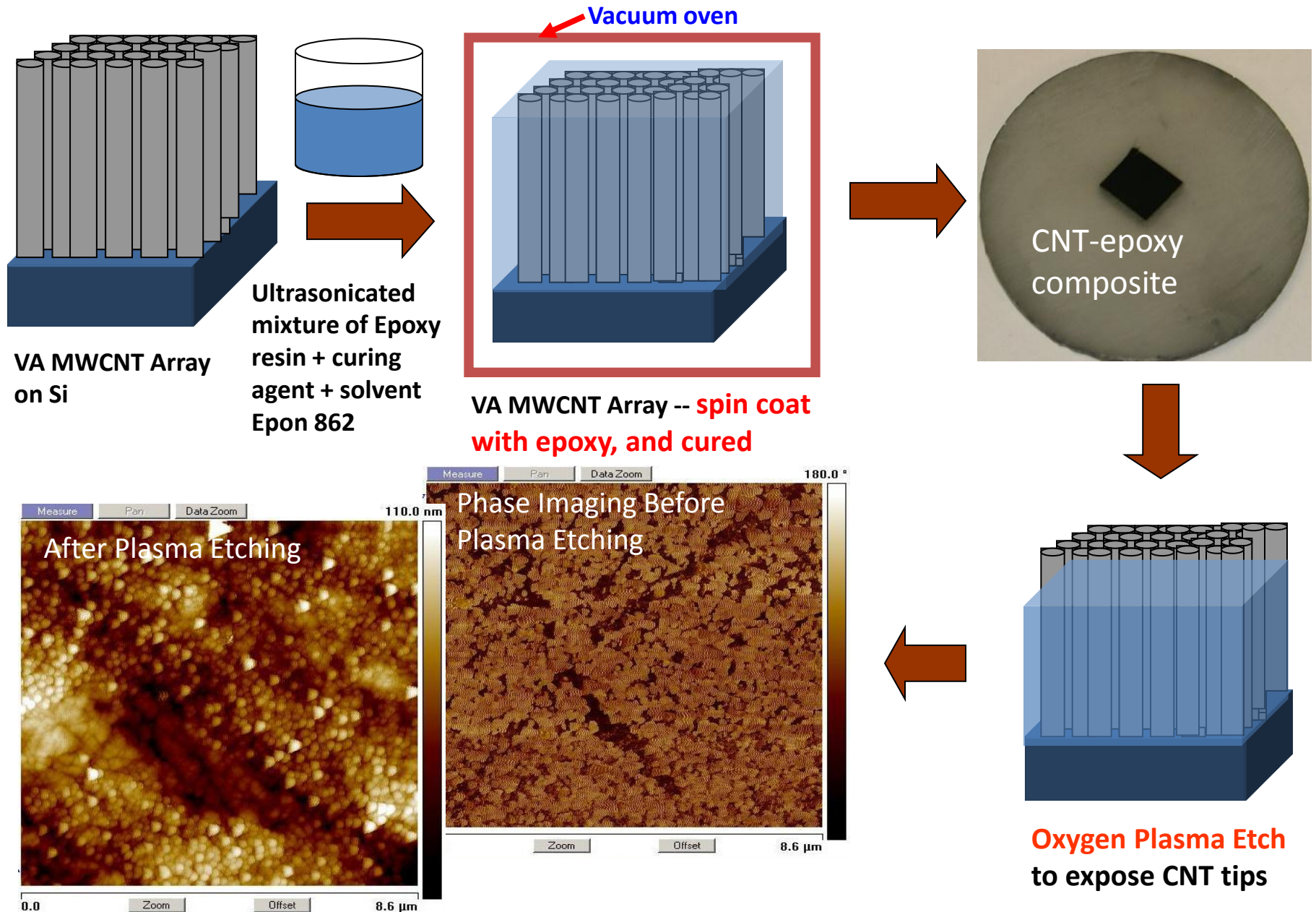
# VA Multi-walled CNT Array



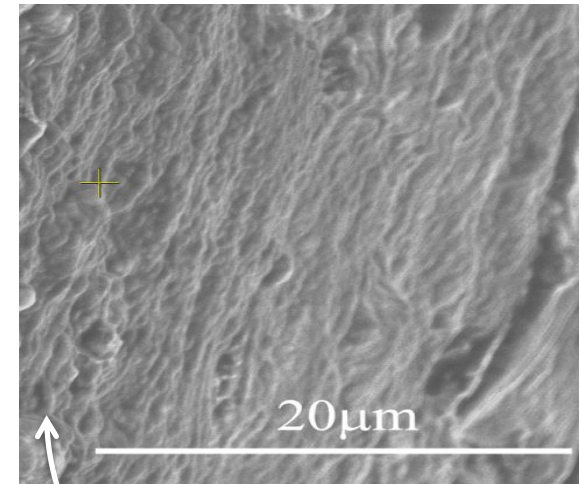
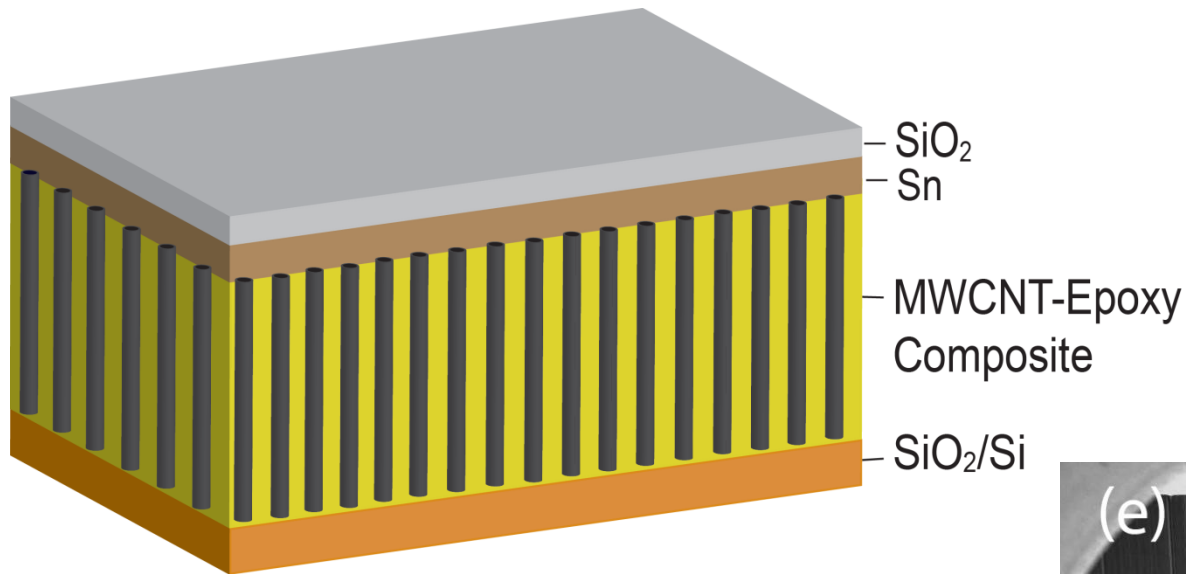
VA MWCNT array of MWCNTs  $\sim 1\text{-}2\text{ mm}$  in length grown by a thermal CVD process (pyrolysis of iron (II) phthalocyanine (FePc) under Ar/H<sub>2</sub> at 900 °C on a silicon wafer). Nanotube dia. 15 to 40nm.



# Fabrication of VACNT- epoxy Composite TIM



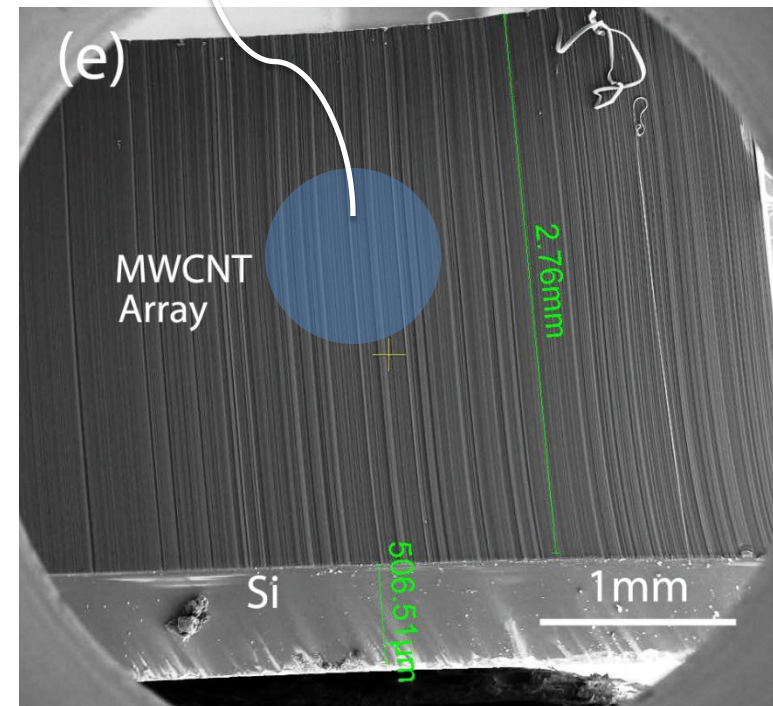
# Vertically Aligned MWCNT-epoxy Composite



## Tasks: Characterize Thermal Transport across MWCNT-epoxy TIM

### Individual components

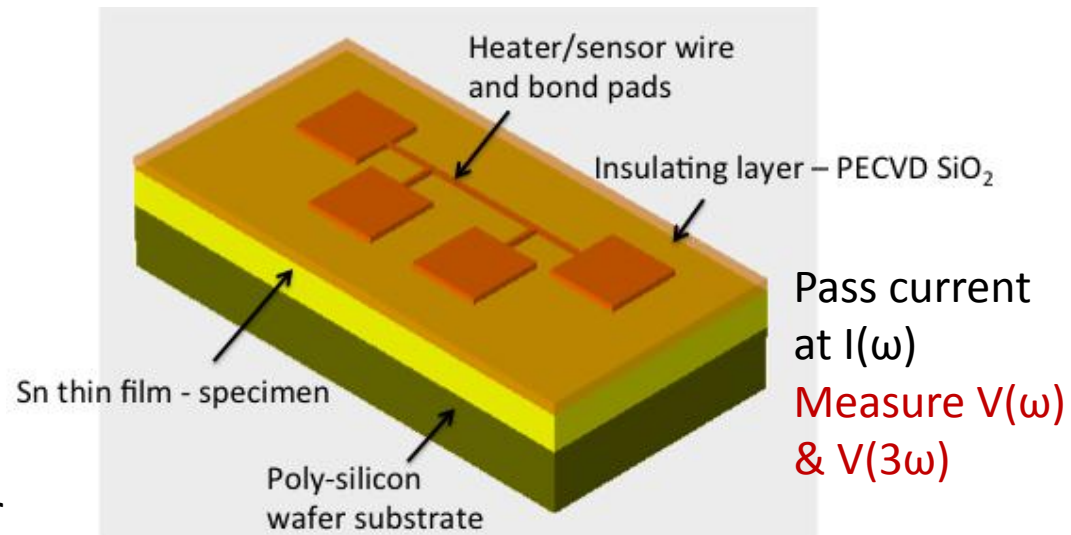
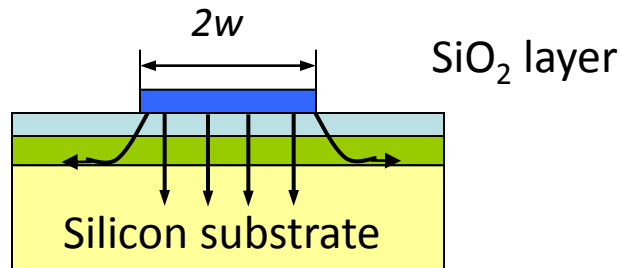
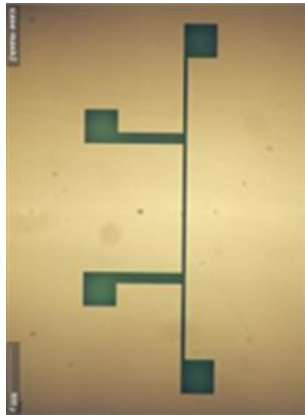
- Individual MWCNTs; epoxy matrix;
- Sn capping layer
- Interfacial thermal resistance at the MWCNT ends & capping Layer





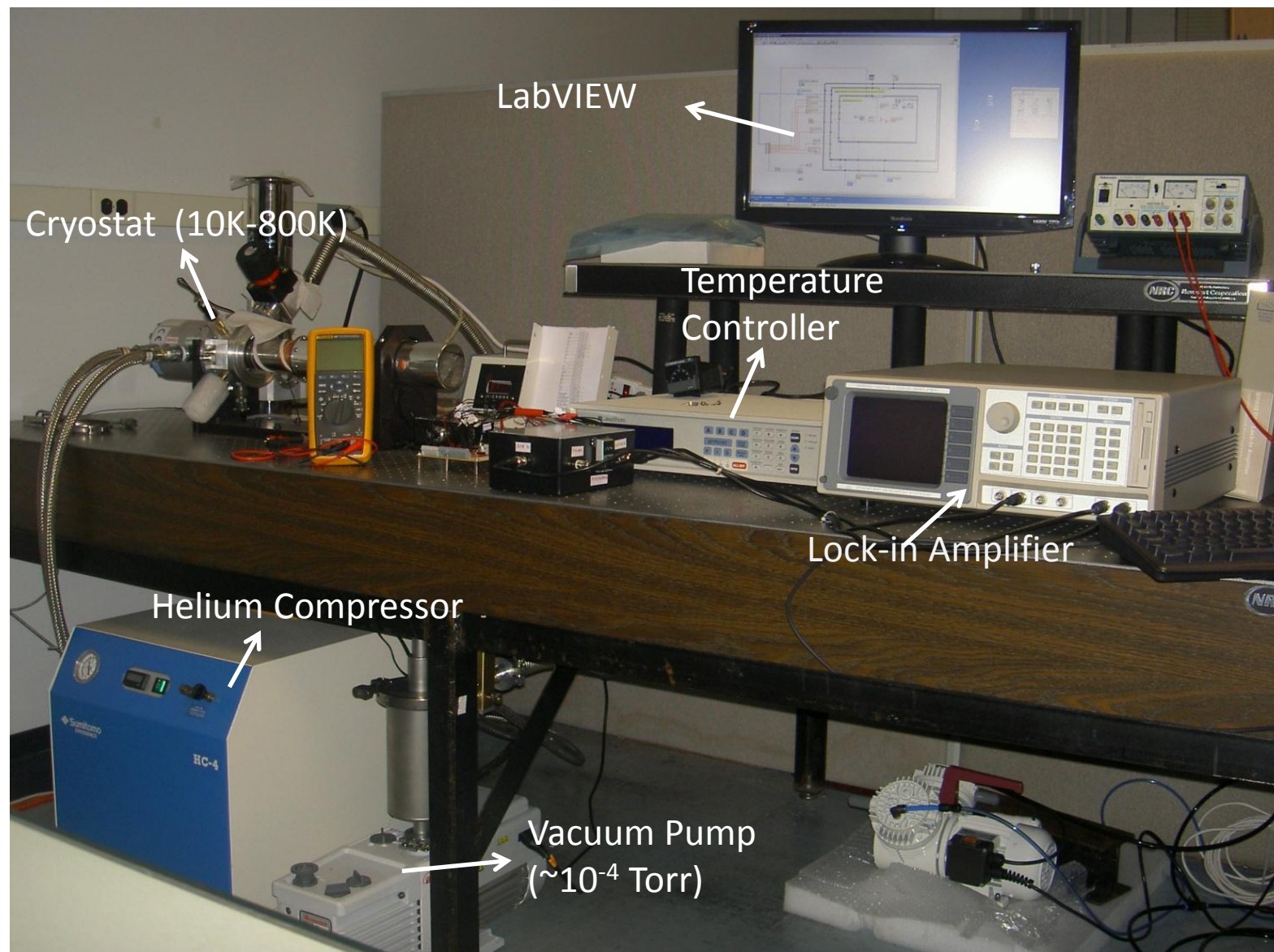
# Thermal conductivity of Tin (Sn) Capping layer -- $3\Omega$ Technique

- 99.999 % pure Sn (100 nm & 500 nm) sputtered on Si substrate at  $2 \times 10^{-7}$  Torr
- Insulating film –  $\text{SiO}_2$  (PECVD using TEOS precursor at  $150^\circ\text{C}$ )
- Heater Lines – deposit Al using magnetron sputtering along with a microfabricated shadow mask



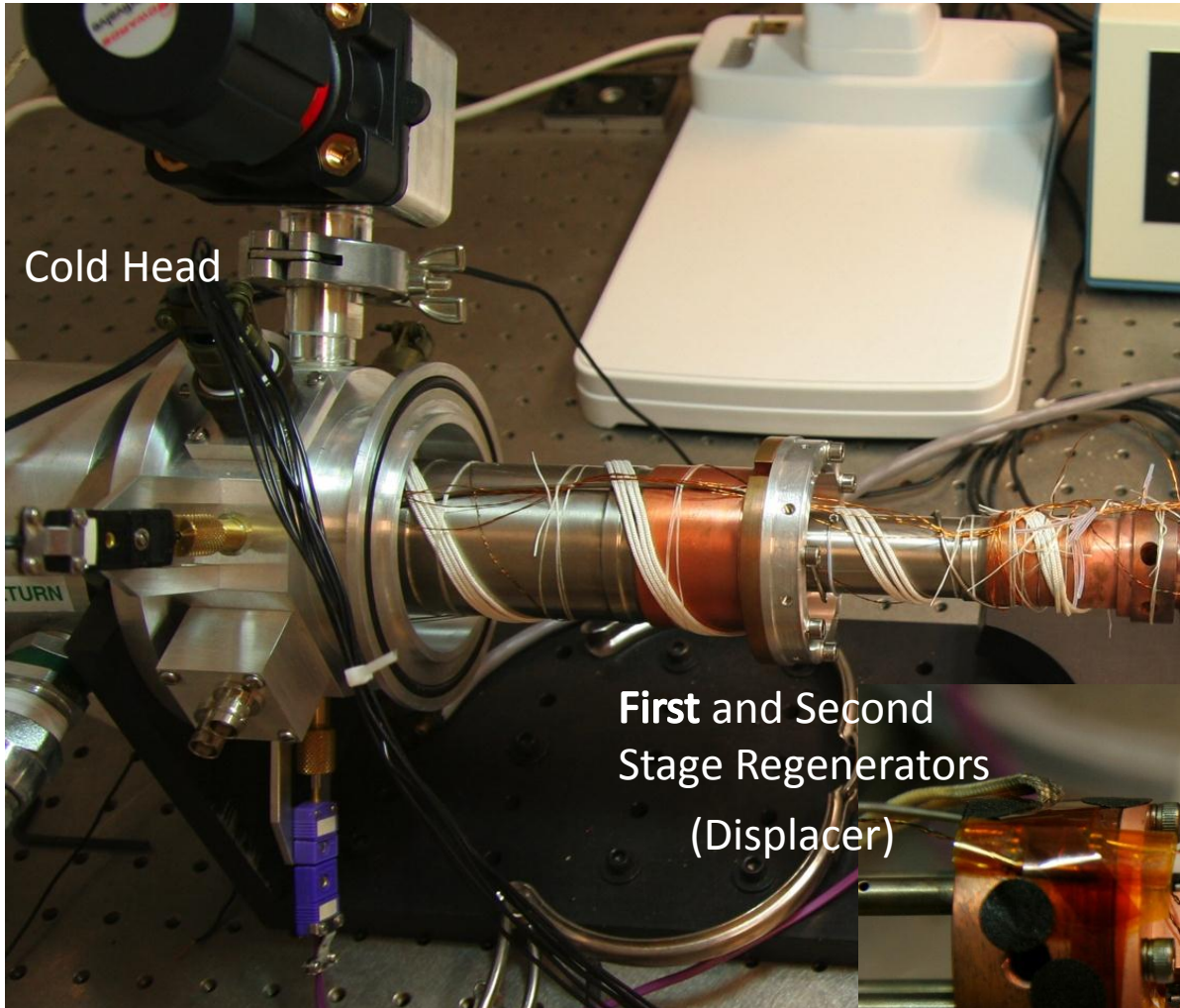
Thin Film Cross-Plane Thermal Conductivity

# 3 $\Omega$ Experimental Setup

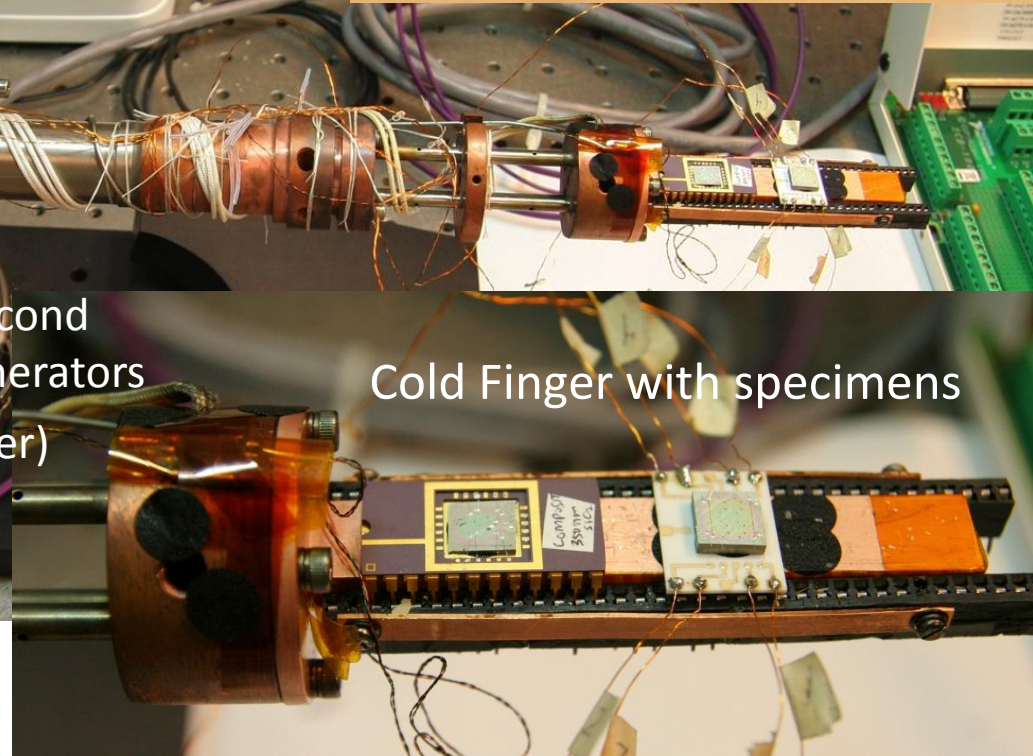
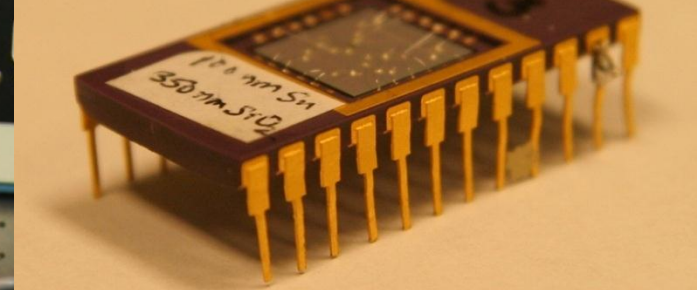




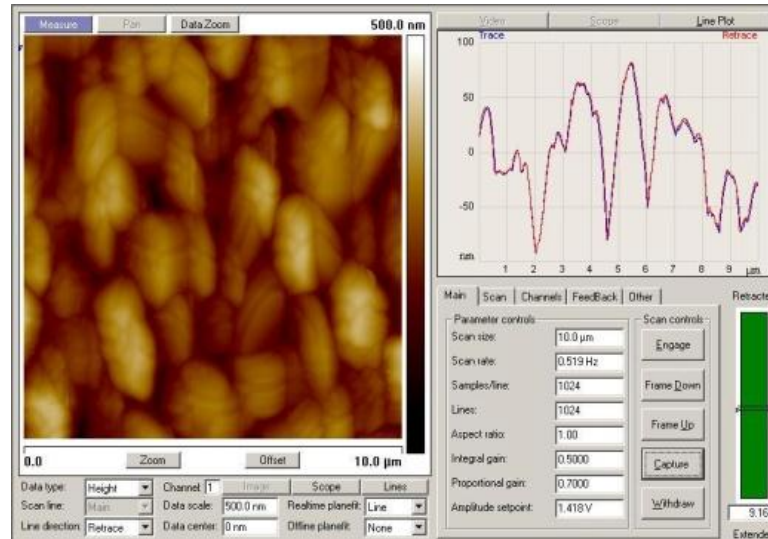
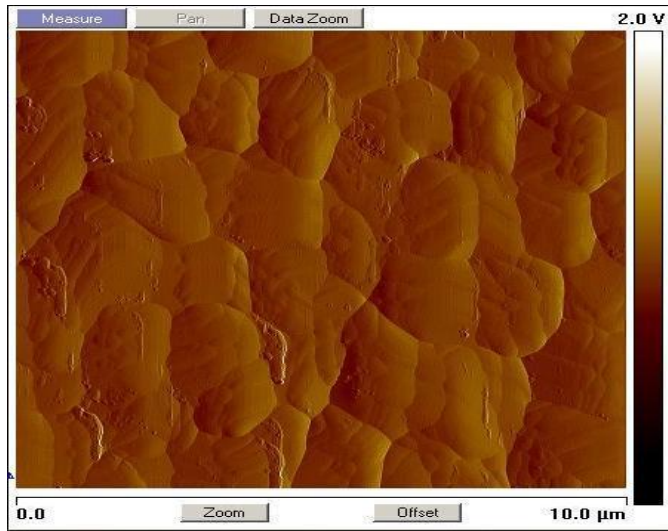
# Cryostat with Specimen



Dip package with  
100 nm Sn sample

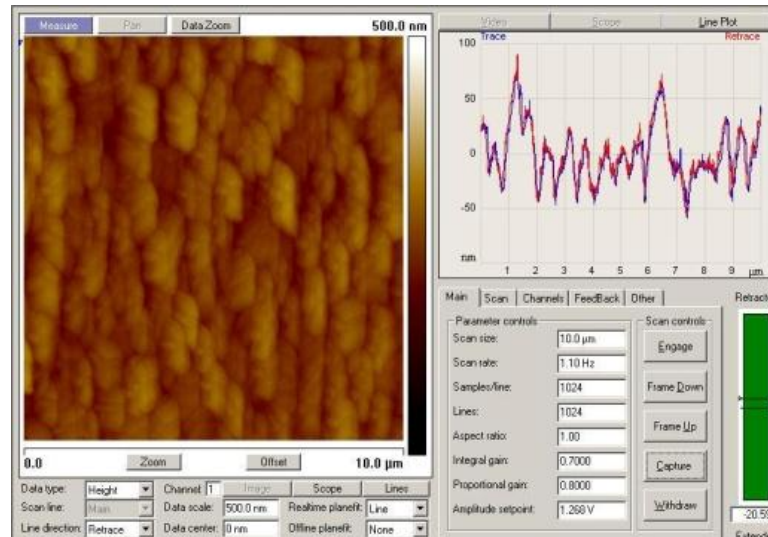
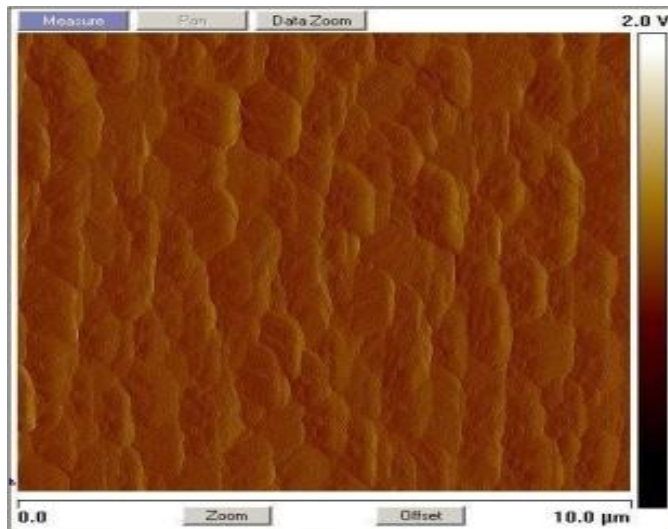


# Sn Thin Film specimens (500 & 100 nm thick)



500 nm Sn film

Grain size:  
450 to 2000 nm



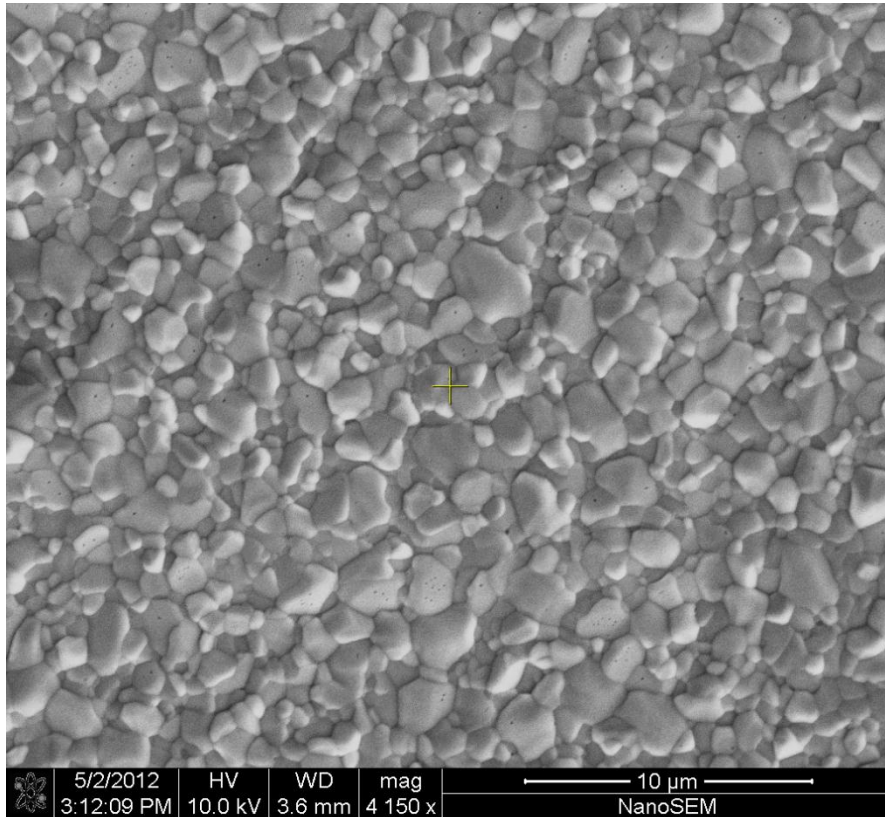
100 nm Sn film

Grain size:  
150 to 600 nm

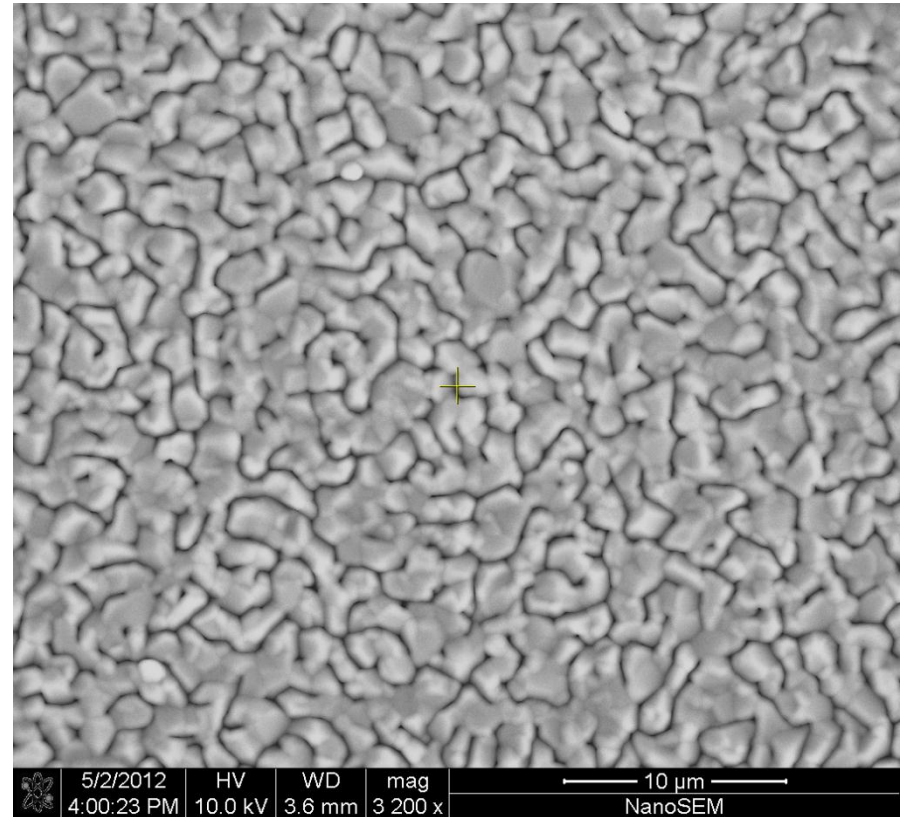
Twin boundaries  
within grains



# SEM Micrographs



500 nm thickness

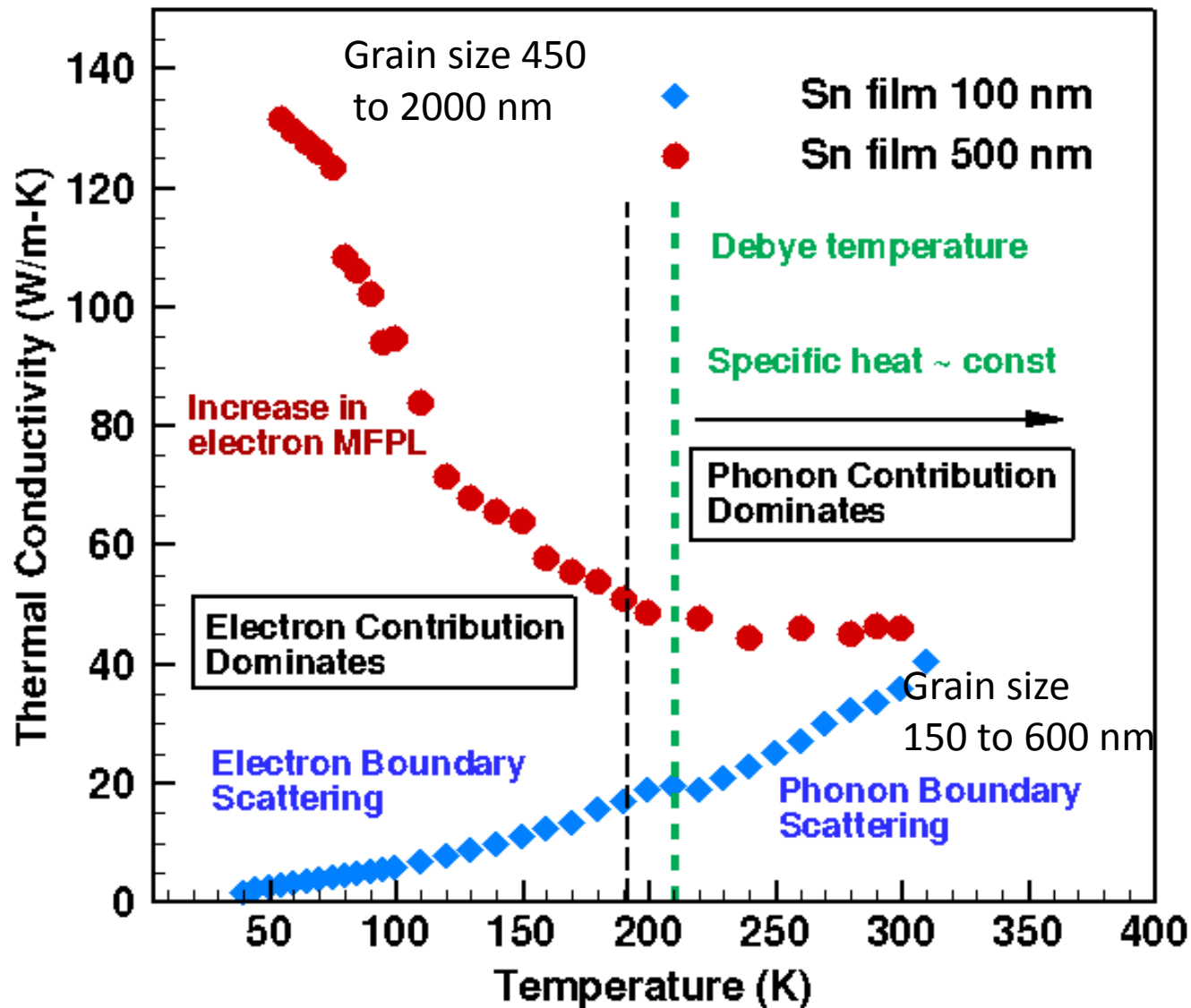


100 nm thickness



# Thermal conductivity of Sn thin Films

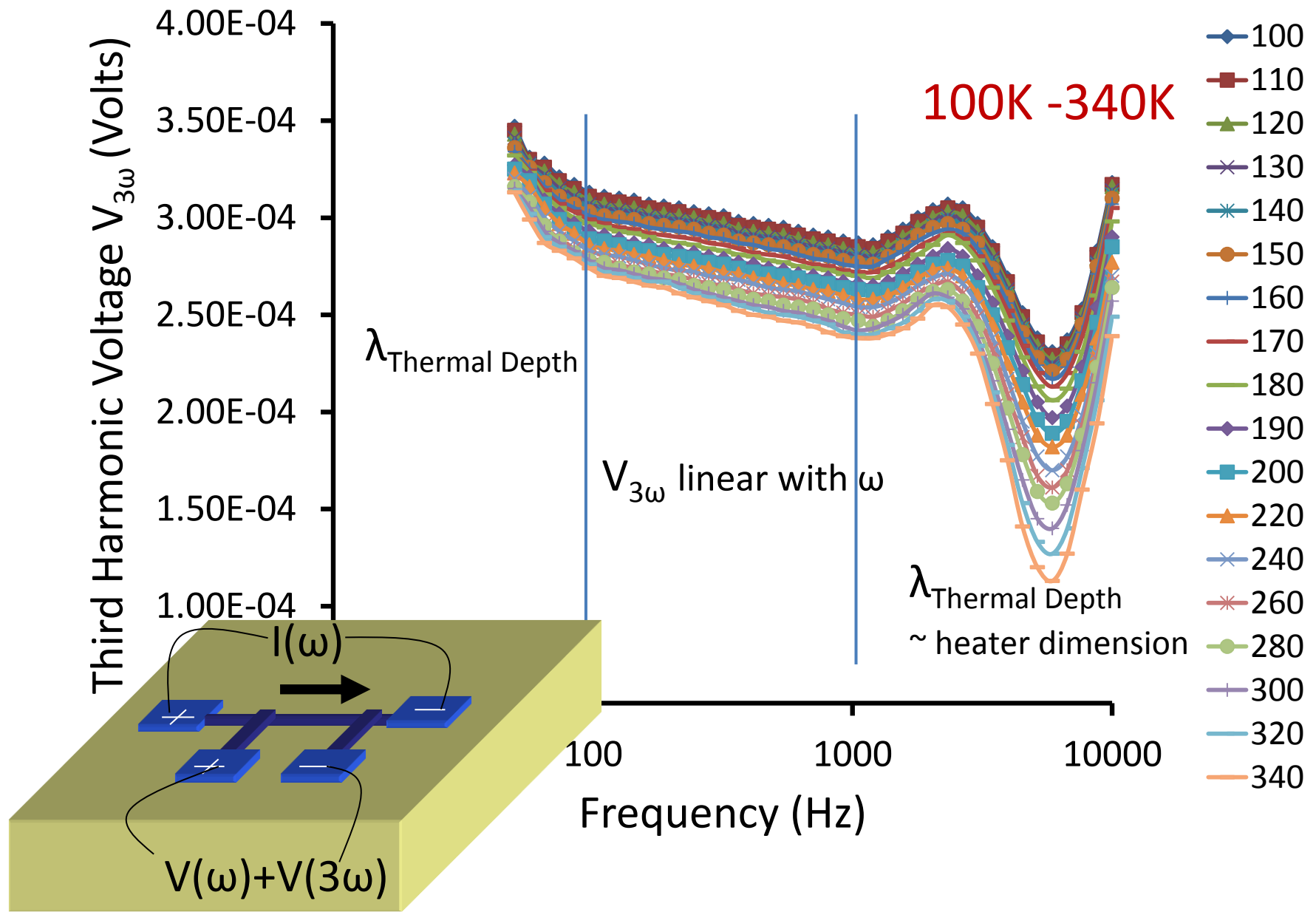
(contribution from both electrons and phonons)

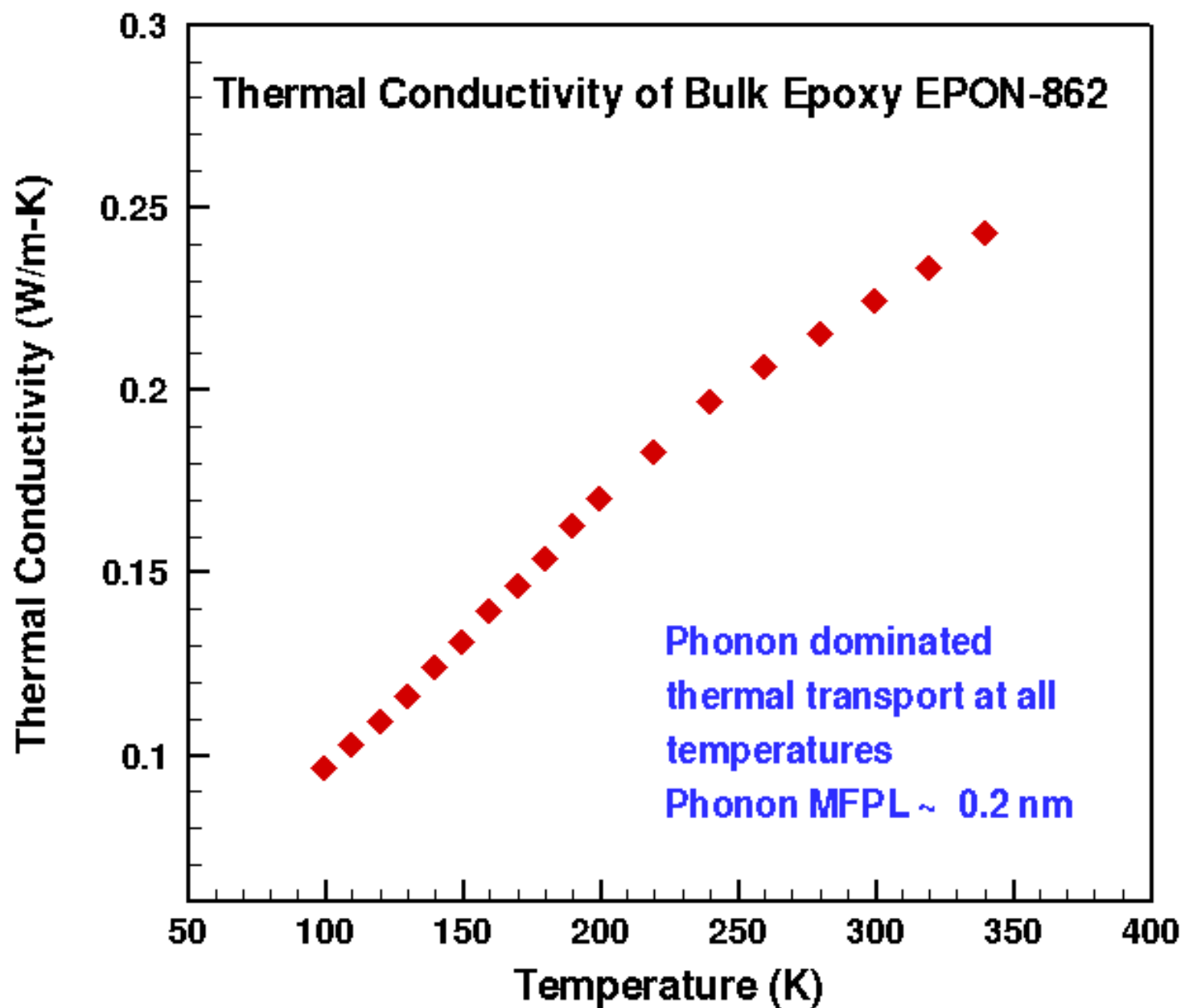


Phonon MFP  
Room temp:  
60 nm

Electron MFP  
(bulk)  
Room temp:  
2.8 nm  
Low temp:  
25 nm

# Thermal Conductivity of Bulk Epoxy (Epon-862)



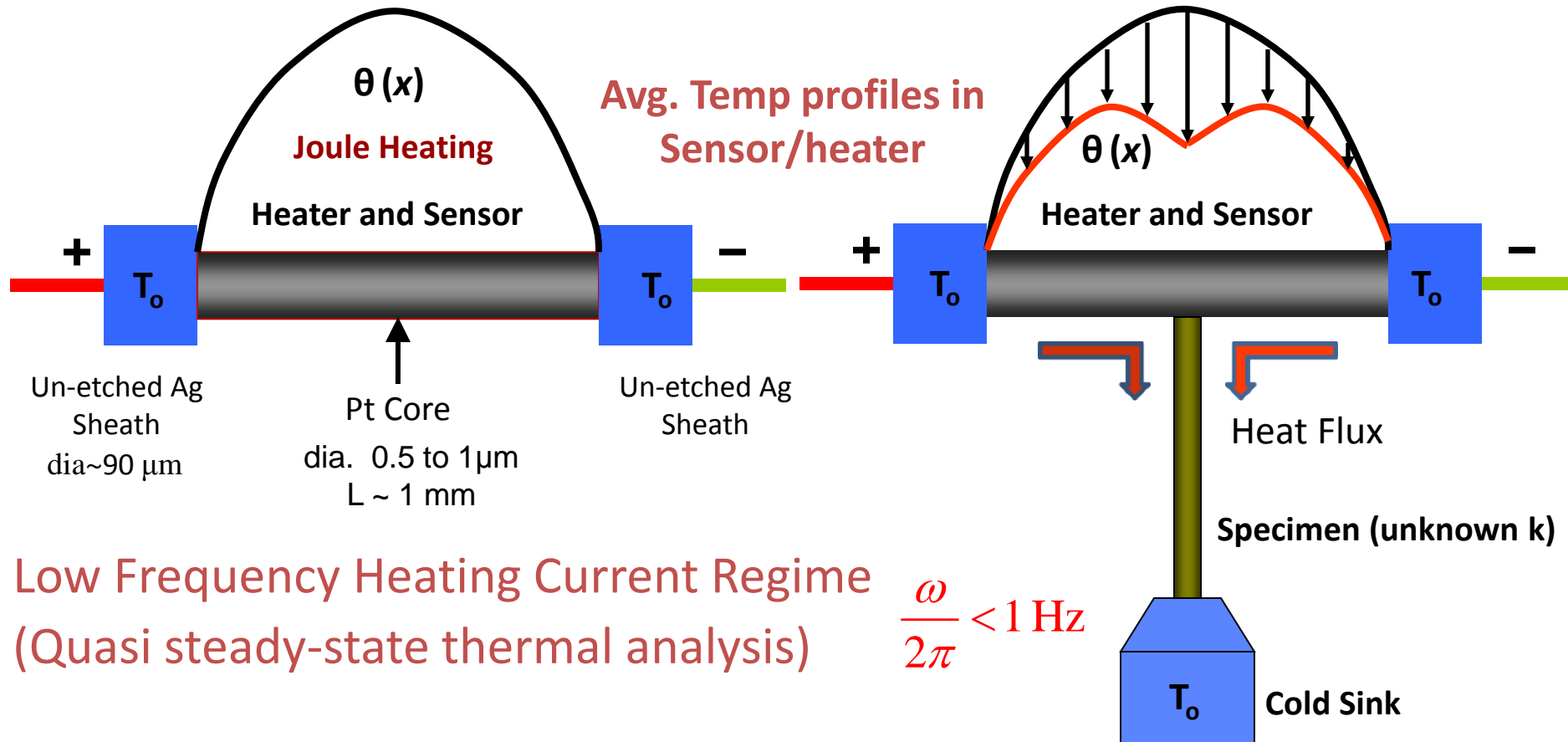


# Thermal conductivity of Individual MWCNTs -- HOT WIRE PROBE

Wollaston wire (Ag/Pt)-- heater and sensing probe

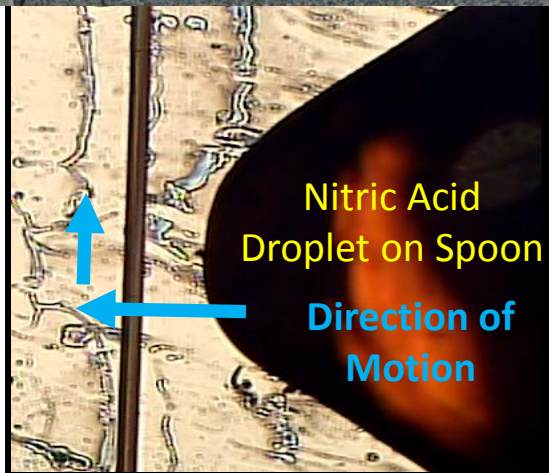
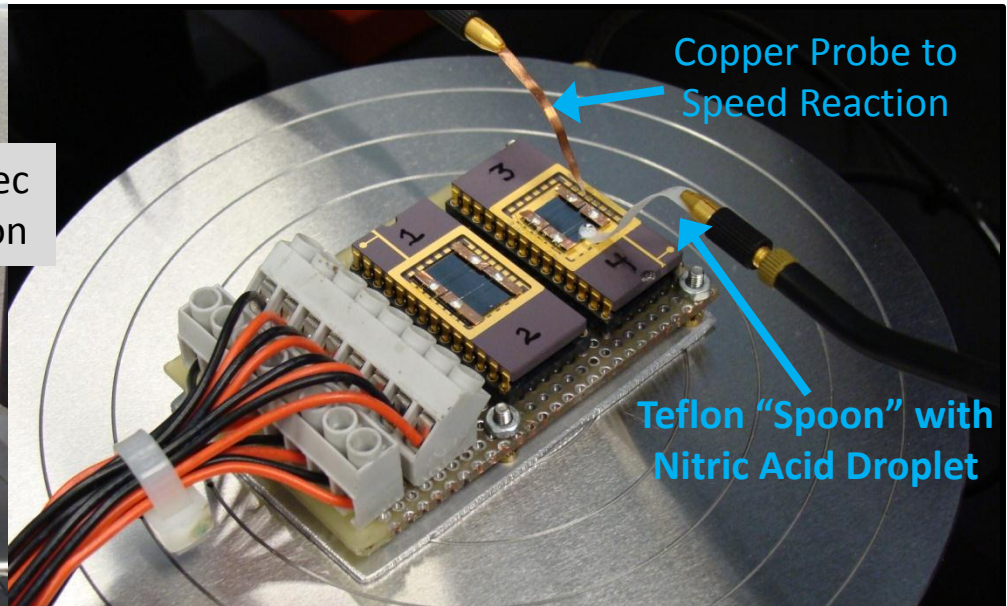
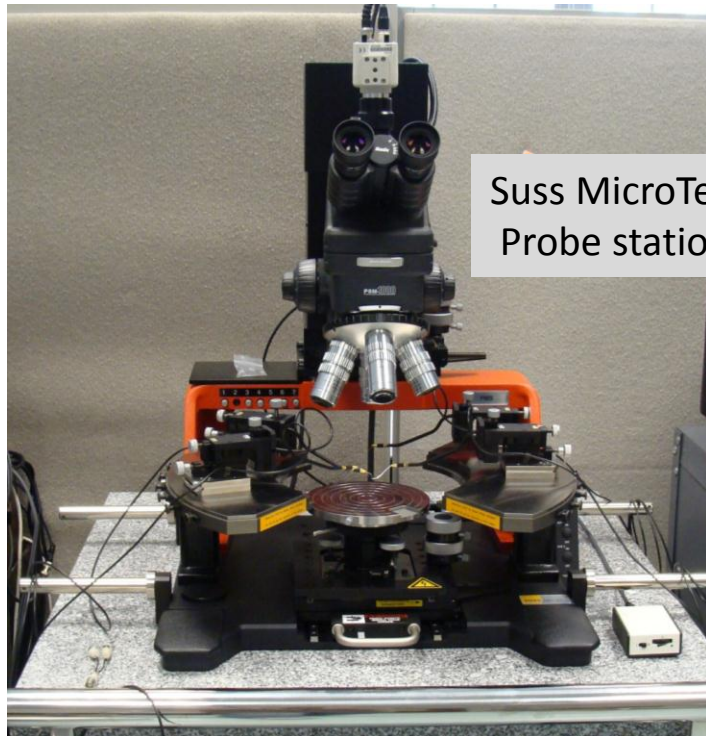
(Along with  $3\Omega$  method)

Sinusoidal current at  $\omega$  leads to Joule heating in Pt. at  $2\omega$ ; Voltage measurements at  $\omega$  and  $3\omega$

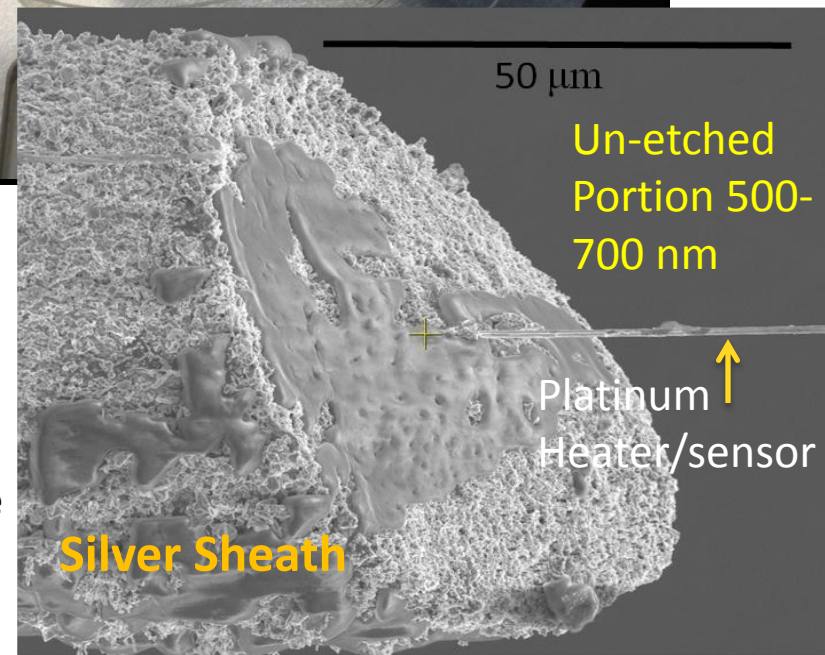


Change in average temperature -- Leads to a change in electrical resistance – leads to change in voltage at  $3\omega$

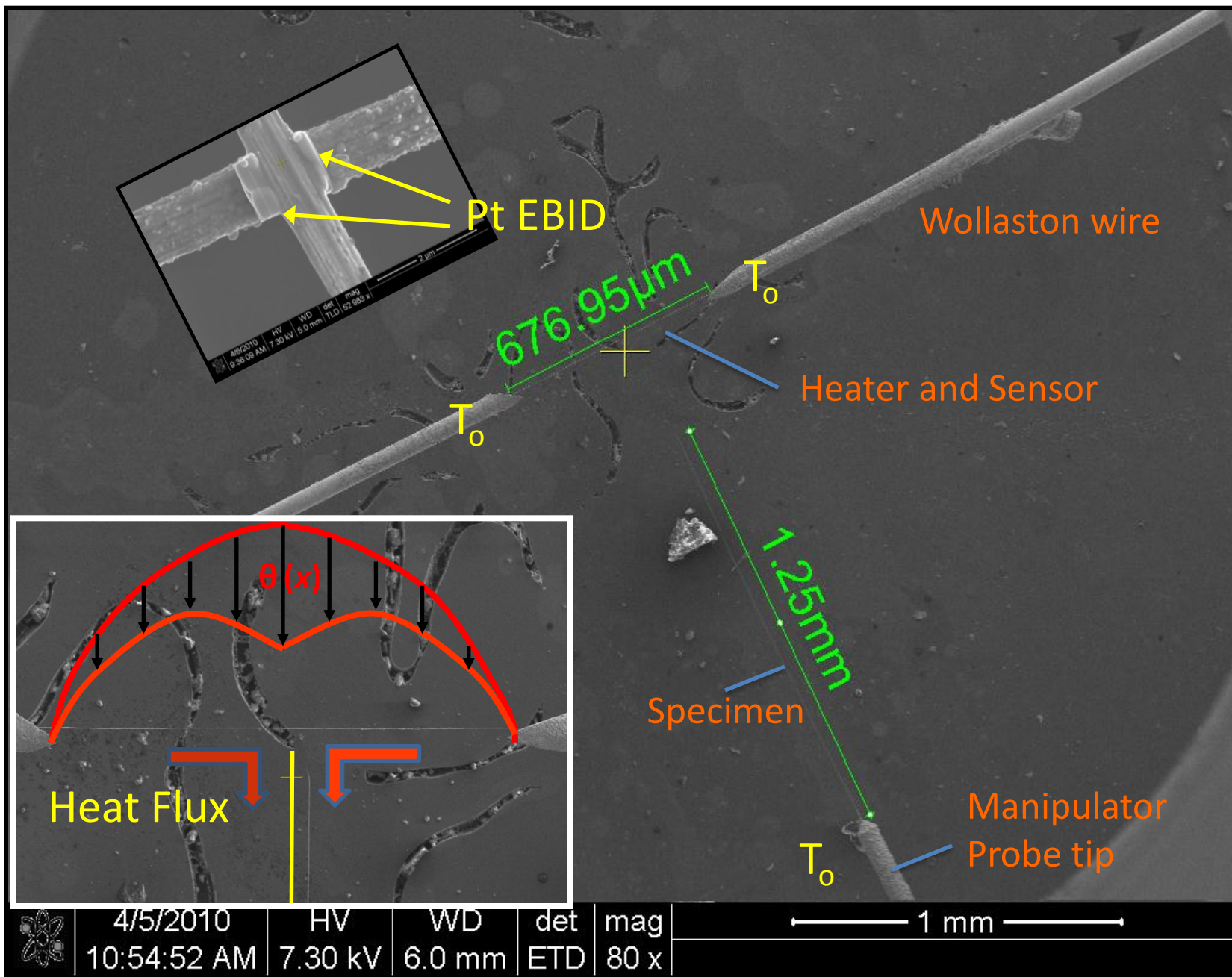
# Etching the Wollaston Wire— Platinum sensor/heater wire



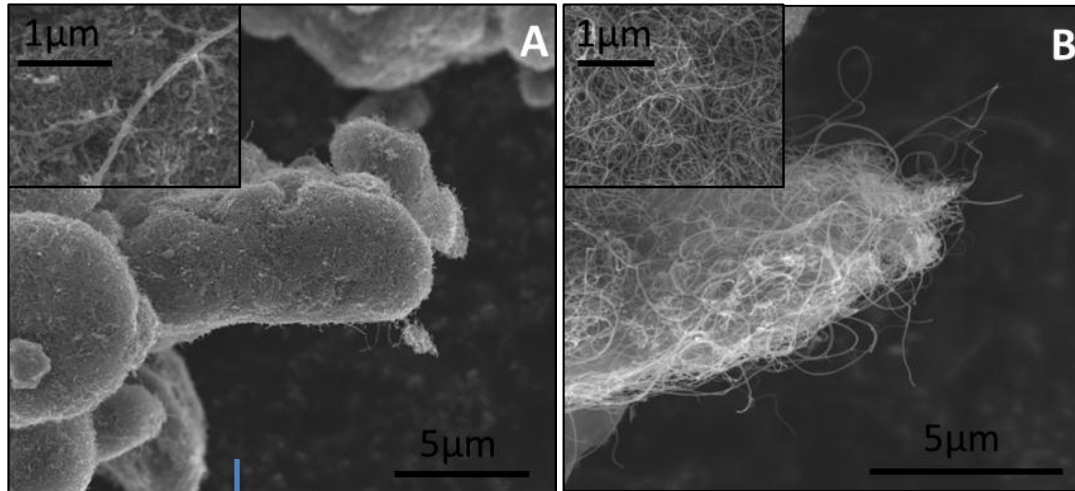
The copper and the  
teflon spoons are  
controlled using two  
micromanipulators in  
a Suss MicroTec Probe  
station







# As-Received & Heat Treated (annealed) MWCNTs

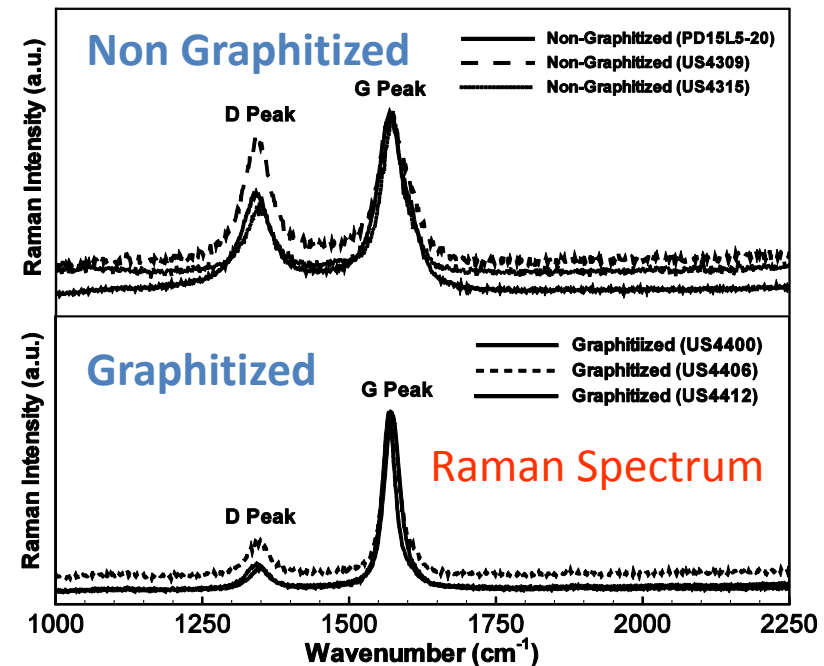


Non graphitized MWCNT  
-- Nanolab Inc  
-- US Nanomaterials Research

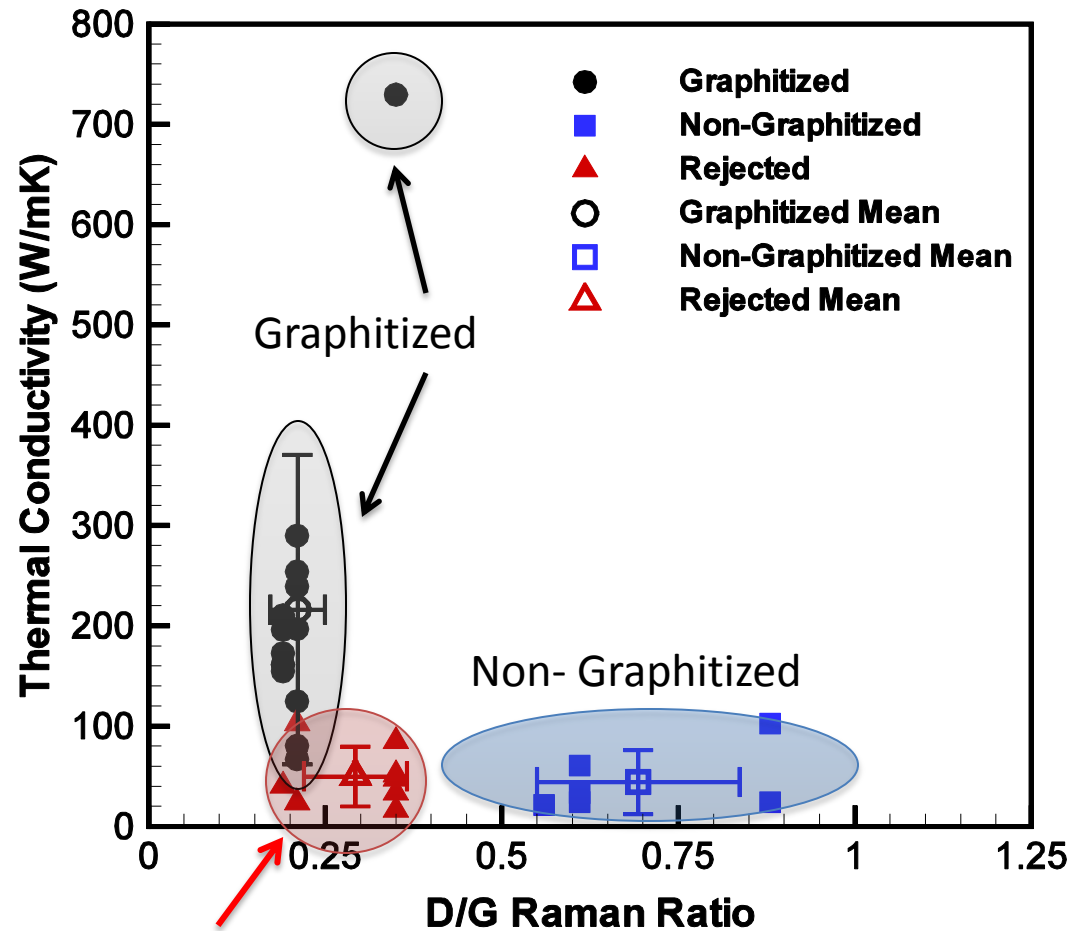
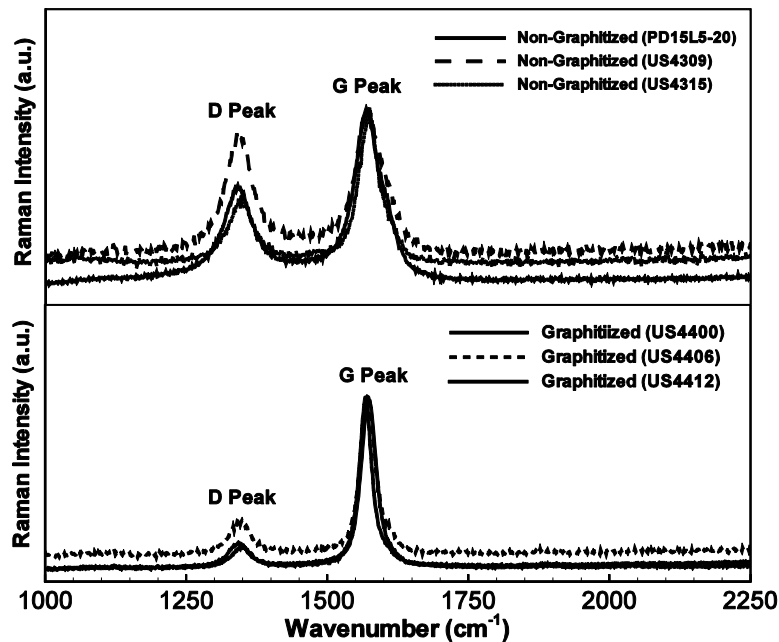
Graphitized MWCNT  
- US Nanomaterials  
Research

20 hour, 3000°C  
Post-annealing heat  
treatment

Smaller D/G ratio  
Less number of defects

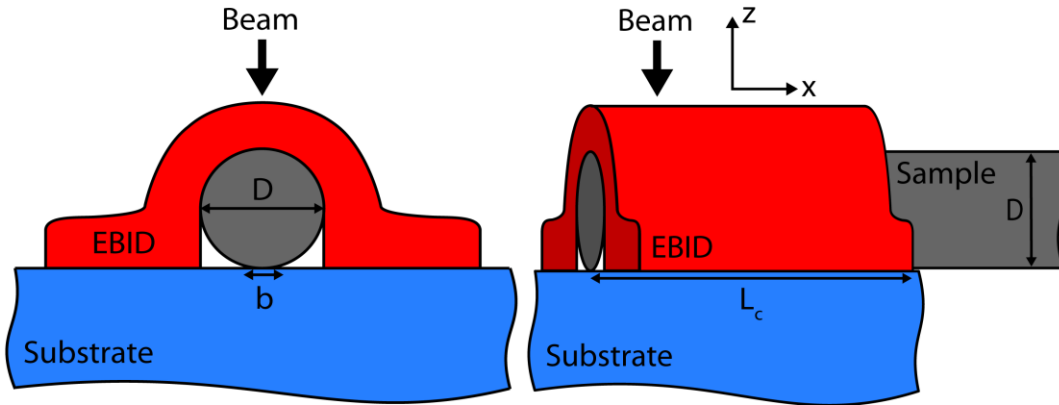


# 3 $\Omega$ Measurements on Individual MWCNTs



Graphitized but with  
morphological defects

# Thermal Contact Resistance at the Pt wire-CNT Junction

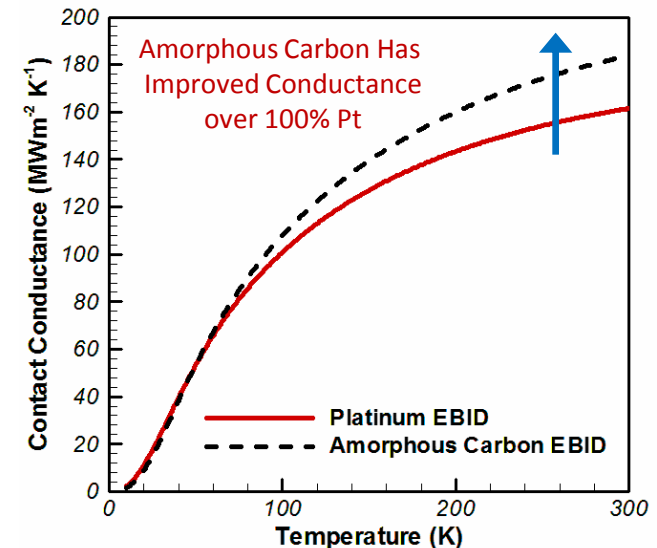
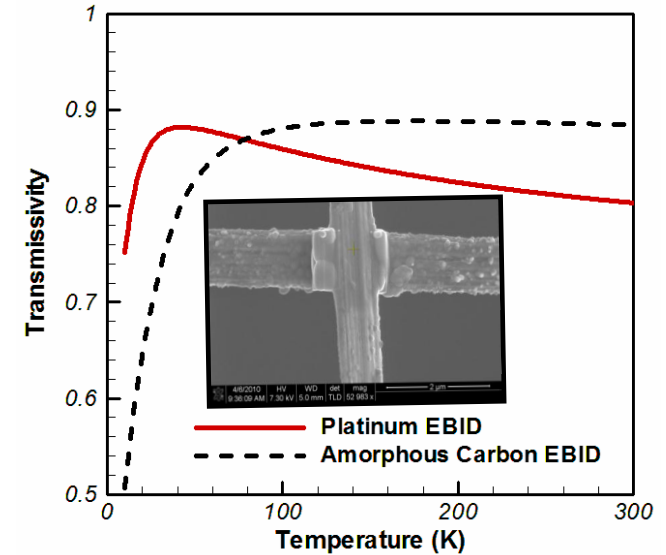


## Required Information

- Phonon dispersion of EBID (Assume Debye Behavior since elastic properties have been measured<sup>4</sup>)
- Phonon dispersion of sample (Assume Graphite)
- Contact width ( $b$ ) estimated from elastic properties assuming van der Waals forces of attraction
- Contact dimensions  $D$ ,  $L_c$ , are measured in SEM

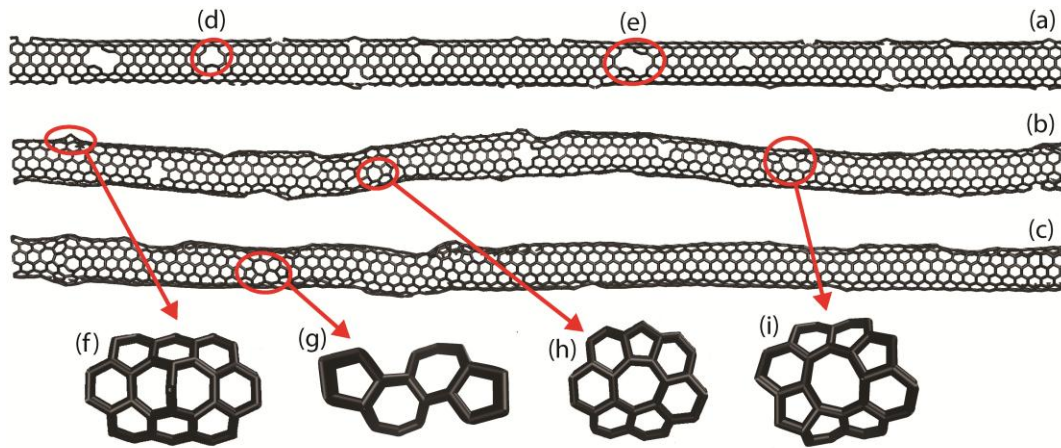
$$\alpha_{1-2} = \frac{\frac{1}{4} \sum_{\omega} \int n \hbar \omega v_2 \text{DOS}_2(\omega) d\omega}{\frac{1}{2} \frac{1}{(2\pi)^2} \sum_{\alpha} \int_{k_z} \int_{k_r} n \hbar \omega v_{1z} k_r dk_r dk_z + \frac{1}{4} \sum_{\omega} \int n \hbar \omega v_2 \text{DOS}_2(\omega) d\omega}$$

$$G_c = \frac{1}{R_c} = \frac{1}{2} \frac{1}{(2\pi)^2} \sum_{\alpha} \frac{d}{dT} \int_{k_z} \int_{k_r} \alpha_{1-2} n \hbar \omega v_{1z} k_r dk_r dk_z$$

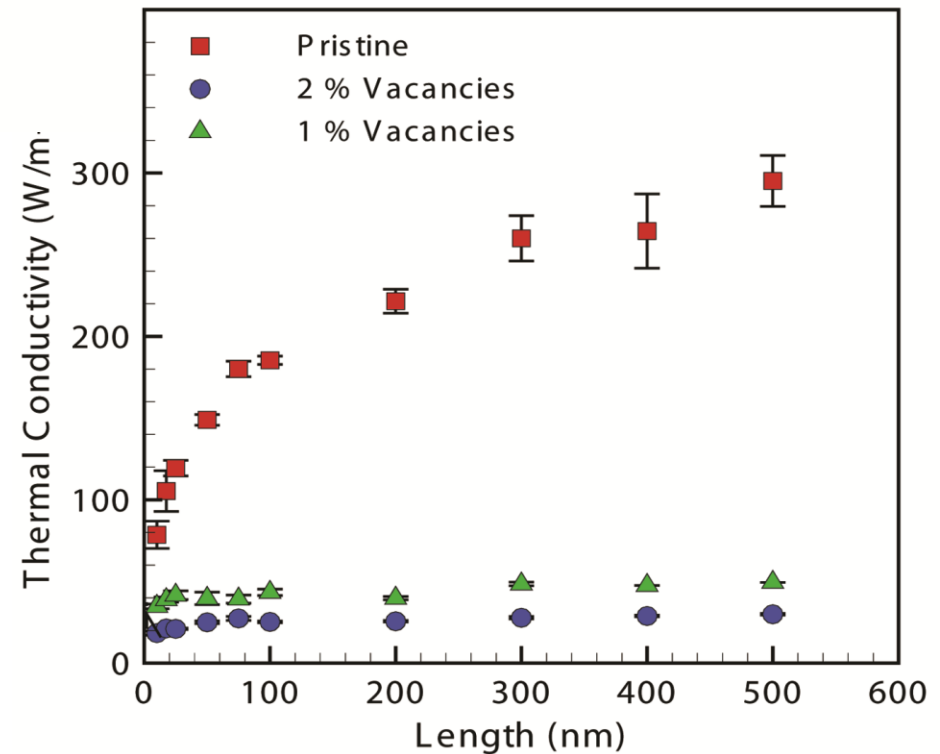


**Correcting for contact conductance, k increases by 5% (Pt EBID)**

# Molecular Dynamics: RNEMD

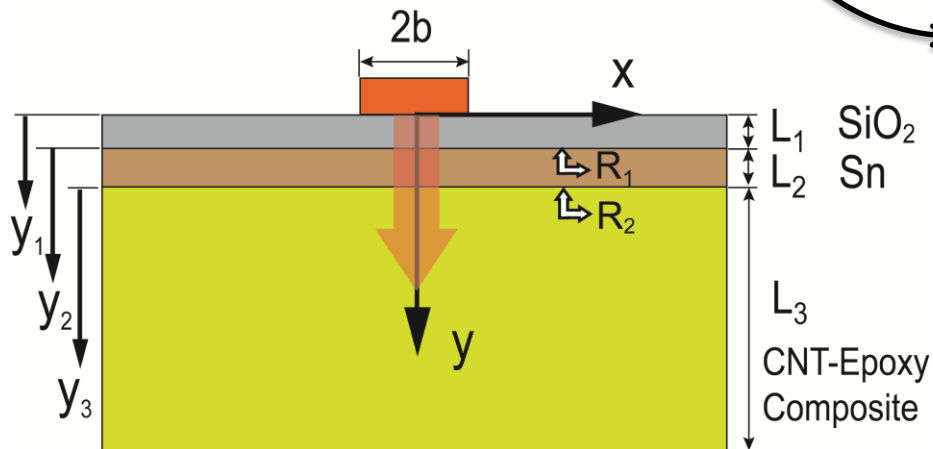
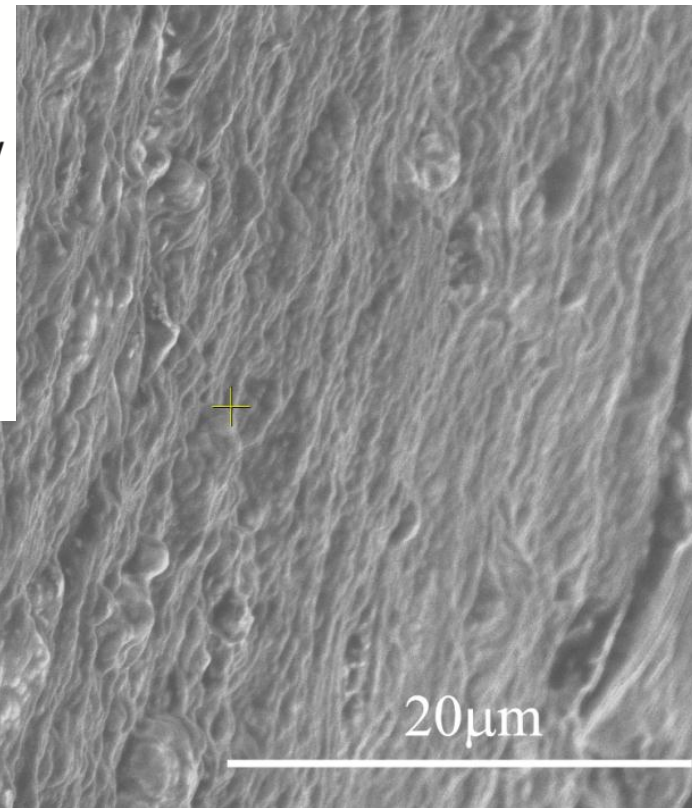
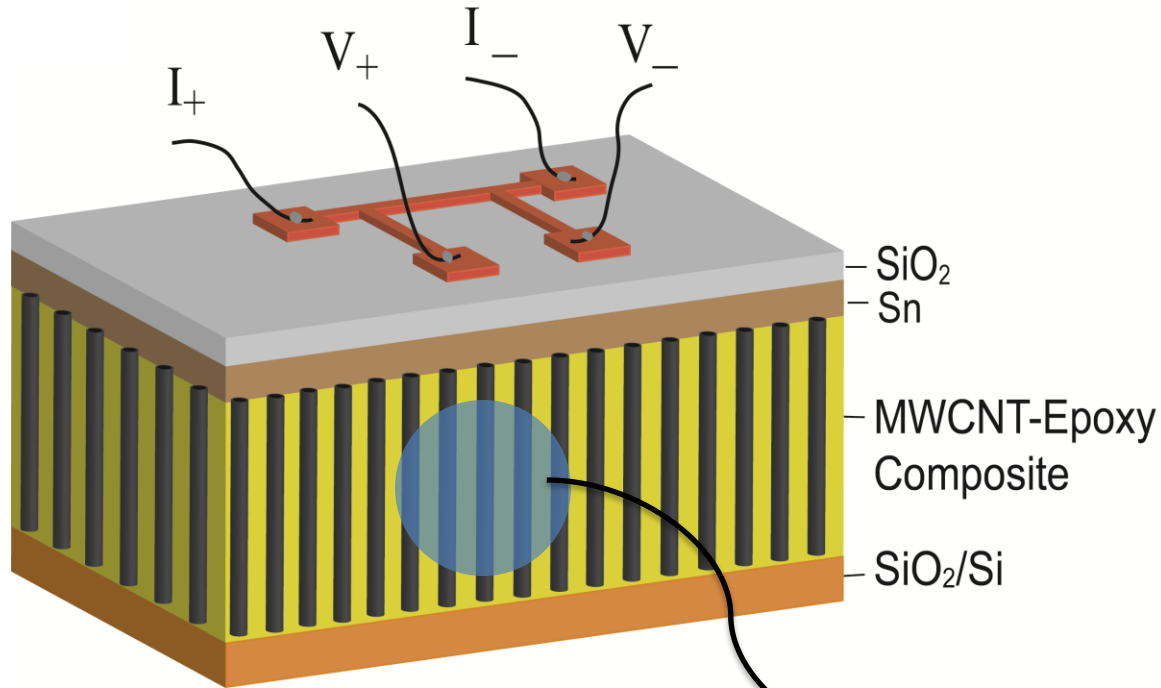


(6,6) armchair SWCNT  
(with and without defects)

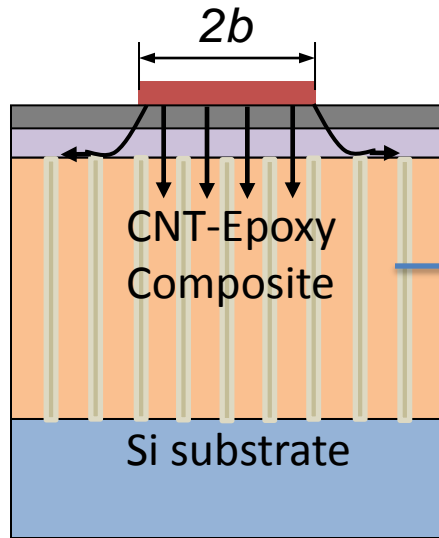




# TIM Thermal Conductivity: 3 $\Omega$ Method



# TIM Thermal Conductivity: 3 $\Omega$ Experimental Results

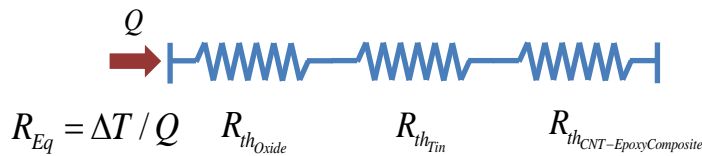


Sample	Thickness	Thermal Conductivity @ RT	Thermal Resistance (L/k)
Oxide	350 nm	1.1 W/m-K	$3.18 \times 10^{-7}$ K/W
Tin	500 nm	46 W/m-K	$1.08 \times 10^{-8}$ K/W
CNT-Epoxy	2.1 mm	5.77 W/m-K	$3.64 \times 10^{-4}$ K/W

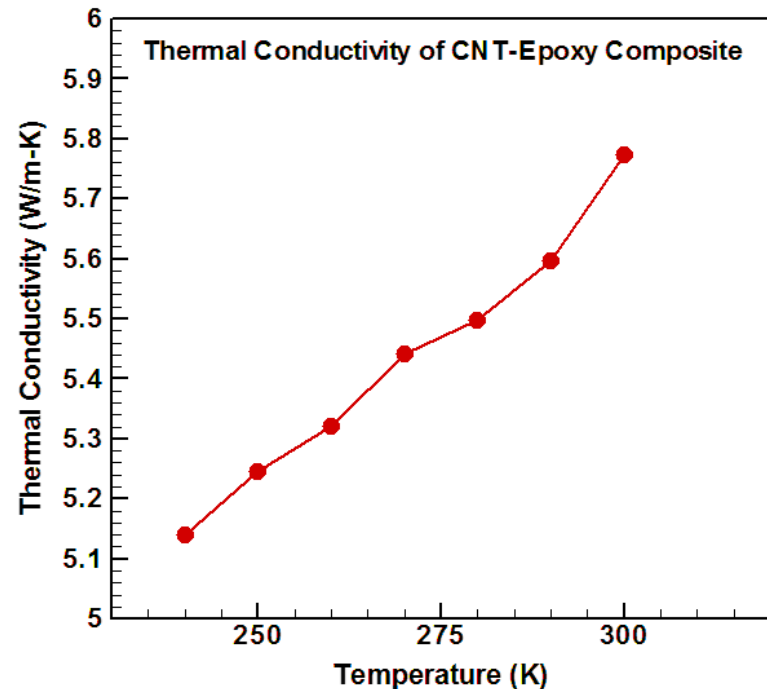
$$k_{system} = \frac{aV_{1W,rms}}{2\rho} \frac{Q_{avg}}{\ell} \frac{\ln(W_2 / W_1)}{V_{3W_1,rms} - V_{3W_2,rms}} \quad \text{MWCNTs } k \sim 60 \text{ W/m-K}$$

- SiO<sub>2</sub> 350 nm
- Sn 500 nm
- CNT-epoxy ~2.1 mm
- MWCNT 15-20 nm Dia
- Si 500  $\mu$ m

## 1D Resistance Network



$$\frac{L_{System}}{k_{System}} = \frac{L_{Oxide}}{k_{Oxide}} + \frac{L_{Tin}}{k_{Tin}} + \frac{L_{CNT-Epoxy}}{k_{CNT-Epoxy}}$$

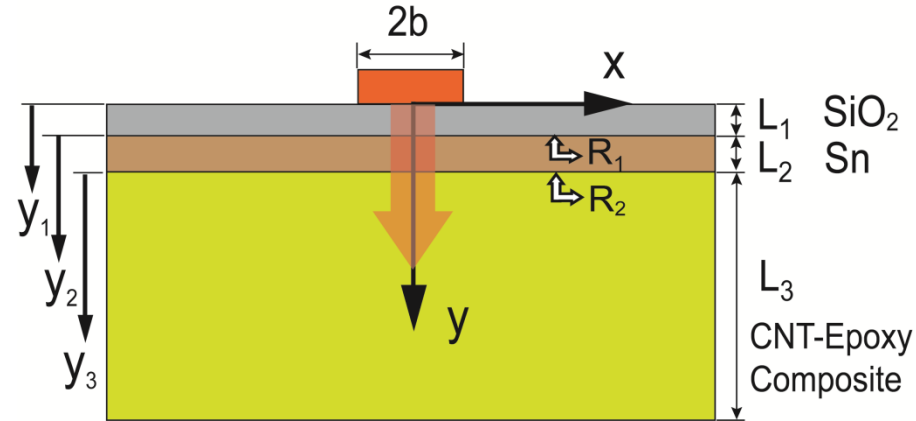


# THERMAL MODEL ( 3 layer 1-D model)

$$T_j(y_j, t) = A.e^{(\eta_j y_j - i\omega t)} + B.e^{(-\eta_j y_j - i\omega t)}$$

$$\eta_j = \sqrt{-\frac{i\omega\rho_j C_{pj}}{k_{y,j}}} \quad \text{(Inverse of the penetration depth)}$$

$$q(y_1 = 0, t) = q_0 e^{-i\omega t} \quad \text{(Heat Flux)}$$



## Thermal Impedance

$$g_j = k_{y,j} h_j$$

$$Z = \frac{T_1(0)}{q_0} = \frac{1}{\gamma_1} \left[ \frac{\left(1 + \frac{\gamma_3}{\gamma_2} \eta_2 L_2\right) + \left(\frac{\gamma_3}{\gamma_1} + \frac{\gamma_2}{\gamma_1} \eta_2 L_2\right) \eta_1 L_1}{\left(1 + \frac{\gamma_3}{\gamma_2} \eta_2 L_2\right) \eta_1 L_1 + \left(\frac{\gamma_3}{\gamma_1} + \frac{\gamma_2}{\gamma_1} \eta_2 L_2\right)} \right] \quad \text{(without Interfacial resistance)}$$

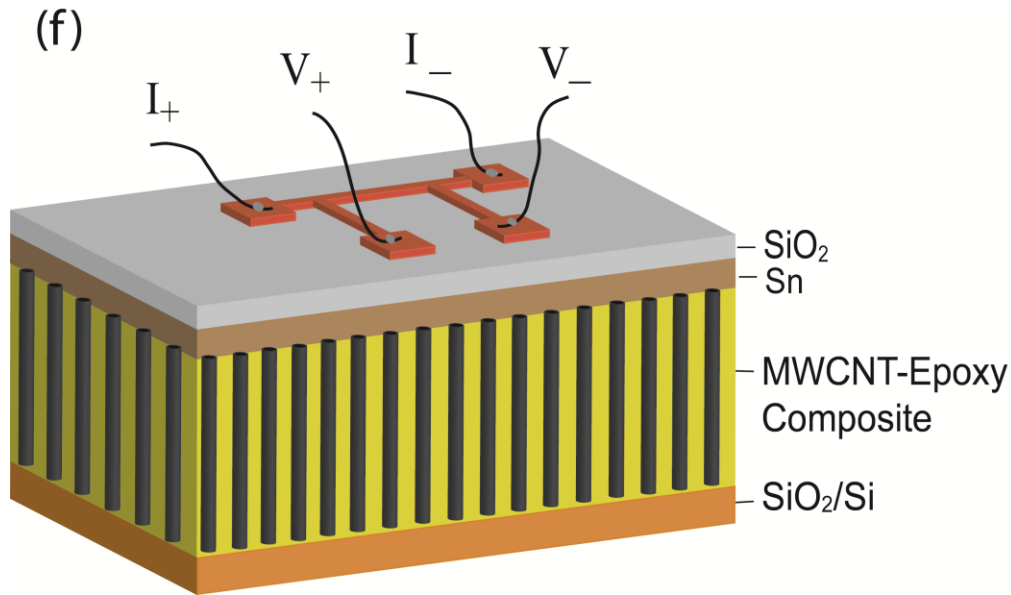
(with Interfacial resistance)

$$Z = \frac{1}{\gamma_1} \left[ \frac{\left[ \left(1 + \gamma_3 R_1 + \gamma_3 R_2\right) + \left(\gamma_2 R_1 + \frac{\gamma_3}{\gamma_2} + \gamma_2 \gamma_3 R_1 R_2\right) \eta_2 L_2 \right] + \left[ \frac{\gamma_3}{\gamma_1} + \left(\frac{\gamma_2}{\gamma_1} + \frac{\gamma_2 \gamma_3}{\gamma_1} R_2\right) \eta_2 L_2 \right] \eta_1 L_1}{\left[ \left(1 + \gamma_3 R_1 + \gamma_3 R_2\right) + \left(\gamma_2 R_1 + \frac{\gamma_3}{\gamma_2} + \gamma_2 \gamma_3 R_1 R_2\right) \eta_2 L_2 \right] \eta_1 L_1 + \left[ \frac{\gamma_3}{\gamma_1} + \left(\frac{\gamma_2}{\gamma_1} + \frac{\gamma_2 \gamma_3}{\gamma_1} R_2\right) \eta_2 L_2 \right]} \right]$$

$R_1$  = Thermal resistance between SiO<sub>2</sub> and Sn

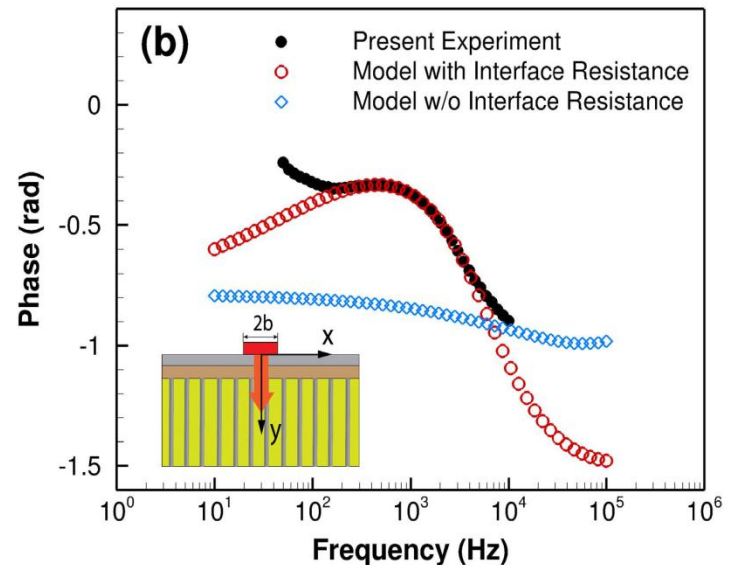
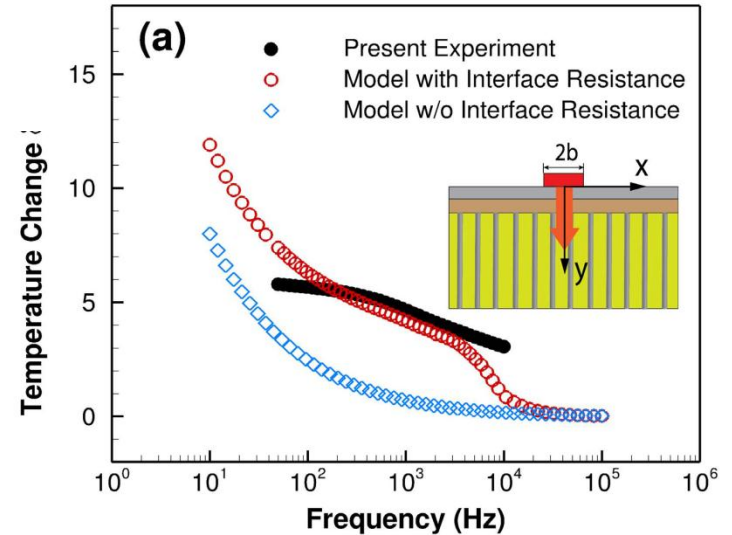
$R_2$  = Thermal resistance between Sn and MWCNT

# Estimate Interfacial Thermal Resistance



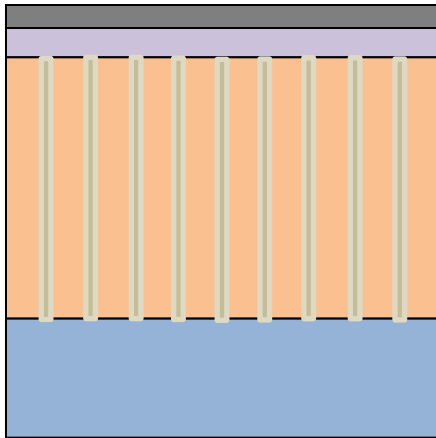
Thermal Interface Resistance between oxide and tin --  $5 \times 10^{-5} \text{ m}^2 \text{ K/W}$

Thermal Interface Resistance between tin and VA MWCNT --  $8 \times 10^{-6} - 8.5 \times 10^{-7} \text{ m}^2 \text{ K/W}$



# Estimate of Composite Thermal Conductivity based on the Rule of Mixtures

$$k_{Eff} = k_{Air} f_{Air} + k_{Epoxy} f_{Epoxy} + k_{CNT's} f_{CNT's}$$

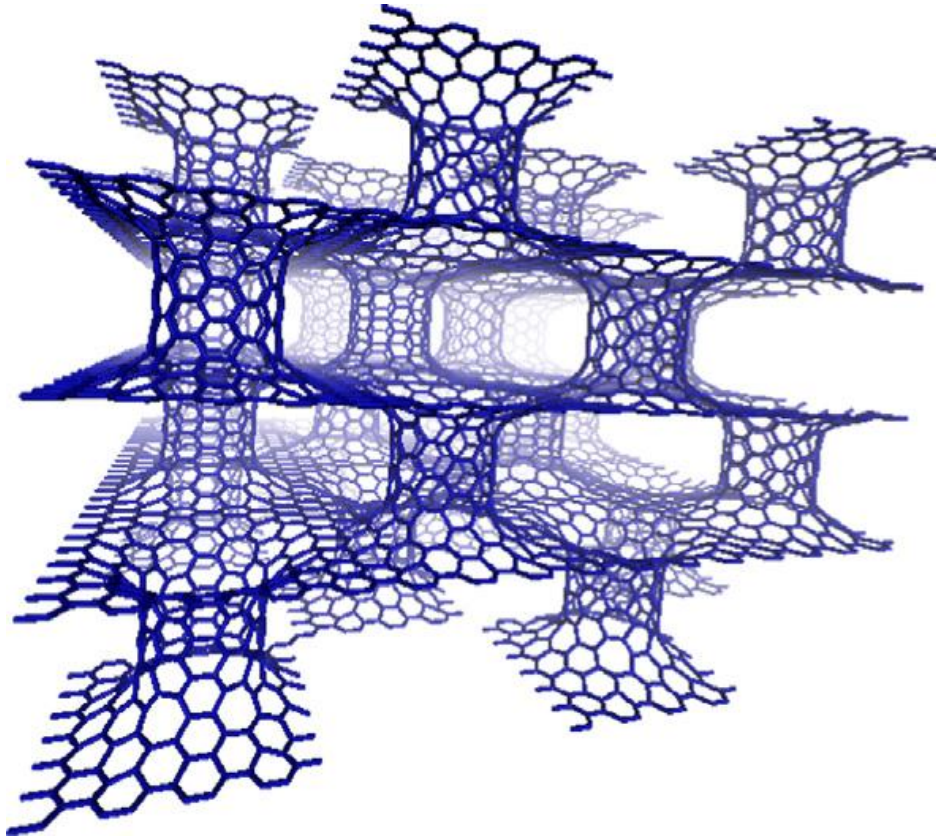


Sample 10 X 11.5 X 2.1 (mm)	Weight %	Density Kg /m <sup>3</sup>	Volume %	Thermal Conductivity
Carbon Nanotubes	12.91%	694	9.726%	<b>60 W/m-K</b> (measured)
Epoxy	86.97%	1090	41.764%	0.234 W/m-K (measured)
Air	0.11%	1.2	48.51%	0.026 W/m-K
CNT-Epoxy Composite				<b>5.77 W/m-K</b> (Measured) <b>5.95W/m-K</b> (predicted)

USE GRAPHITIZED VA MWCNT ARRAYS -- Can Push  $K_{TIM} \sim 20 \text{ W}/(\text{m-K})$



# 3-D TIMS: Pillared Graphene-CNT Networks



**Provides avenues for both in-plane  
and cross-plane thermal conductivity**

- Inter-pillar distance
- Pillar length
- CNT-graphene nodes (junctions)

